

ECE 340: Semiconductor Electronics

Practice problems for chapter 1 to 4

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1. In an n-type silicon wafer ($N_d = 10^{17} \text{ cm}^{-3}$) illuminated uniformly with 10 mW/cm^2 of red light ($E_{ph} = 1.8 \text{ eV}$). The absorption coefficient of red light in silicon is 10^{-3} cm^{-1} . The minority carrier lifetime is 10 ns .

- (a) Calculate the electron and hole densities
- (b) Calculate the positions of the quasi-Fermi levels for the two carrier types and compare it to the Fermi energy in the absence of illumination.
- (c) If the light was turned off at $t = 0$, find a formula for excess hole concentration $\delta p(t)$ for $t > 0$. Does low level injection condition satisfied in this case?

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2. Image at one end of a n-type silicon, all minority carriers are constantly swept out (i.e. $p=0$ at $x=0$), while the majority carrier remains the same. The doping concentration is 10^{15} cm^{-3} . The hole mobility is $1000 \text{ cm}^2/\text{V-s}$, $\tau_p = 1\mu\text{s}$, $T=300\text{K}$. For simplicity, assume $KT/q=25\text{mV}$ at 300K .

- What is the excess hole concentration δp at $x=0$?
- Find the minority carrier concentration distribution $p(x)$ and sketch $p(x)$ vs x .
- At $x = 50\mu\text{m}$, calculate the hole diffusion current.



3. A silicon crystal is known to contain 10^{-4} atomic percent of arsenic (As) as an impurity. It then receives a uniform doping of 2×10^{16} phosphorus (P) atoms and a subsequent uniform doping of 1×10^{16} Gallium (Ga) atoms. A thermal annealing treatment then completely activates all impurities. (silicon has $5 \times 10^{22} \text{ atoms cm}^{-3}$, intrinsic carrier concentration for silicon is $1.5 \times 10^{10} \text{ cm}^{-3}$)

- What is the conductivity type of this silicon sample?
- What is the electron and hole concentration?
- Find the location of the Fermi-level.

4. A silicon bar with height of $h=100\mu\text{m}$, width $W=1\text{cm}$ and length of $L=10\text{cm}$, was doped by diffusion. The doping profile is $N_d(x) = N_0(1 - x/h)$, where $N_0 = 10^{15}\text{cm}^{-3}$. Calculate the resistance of this bar along the length direction. Assume mobility is uniform $\mu_n=1000\text{cm}^2/\text{V}\cdot\text{s}$.

